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Form PTO-14	ATTY. DOCKET NO. MI22-2438			SERIAL NO. PRIORITY 09/602,381						
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	AB	5,436,481	07-1995	Egawa et al.				٠	٠.	
	AC	5,378,645	01-1995	Inoue et al.				٠		
	AD	5,258,333	11-1993	Shappir et al.						
	AE	5,518,946	05-1996	Kuroda						-
	AF	5,445,999	08-1995	Thakur et al.				٠٠,	. 10	
	AG	5,382,533	01-1995	Ahmad et al.			·		*,	
	AH	5,663,077		Adachi et al, ., .		• .		,6	3. 30	٠.
7.7.	Al	5,026,574	206-1991*	Economu et al.,			·	i,	<u>;</u> >.	٠
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war no no fama	AK	5,719,083	02-1998	Komatsu	re ne, reces e see			ň	. 1	
AG	AL	5,760,475		Cronin				. ن	tr	·
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10	АТ	Ko, L. et al., "The	Effect of Nitro	gen Incorporation into the Gate	Oxide by Using Shall	low Implant	ation o	of Nitro	gen and Dri	ive-In
NO		Process*, IEEE	1996, pp. 32-35	57				,		
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	АВ	5,619	,057	04-1997	Komatsu						
	AC	5,633	,036	05-1997	Seebauer et al.						
	AD	6,054	,396	04-2000	Doza	_					
	AE	6,174	,821	01-2001	Dosn		2				
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1	AK,	5,972	783	10-1999	Arai et al.	·			:		
AG	AL	6,093	,661	07-2000 -	Trivedi et al.						
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	AC	5,596,218	01-1997	Soleimani et al.					
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	AĒ	6,207,532 Bi	03-2001	Lio et al.					
	AF	6,114,203	09-2000	Ghidini et al.			:		
	AG	6,110,842	08-2000	Okuno et al.			<u>:</u>		
	АН	6,091,110	07-2000	Hebert et al.			·	ļ:	
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	AJ	6,140,187	10-2000	DeBusk et al.					•
	AK	6,197,701	03-2001	Shue et al.					
Re	AL	6,091,109	07-2000	Hasegawa					
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		LIST OF ART CITED BY APPLICANT (Use several sheets if accessary)			APPLICANT Micron Technology,					
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	AB	5,685,949	11-1997	Yashima						
	AC	6,268,296 B1	07-2001	Misium et al.					iz	
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	AE	6,255,703 B1	07-2001	Hause et al.				:	•	
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	ΑG	6,228,701 B1	05-2001	Dehm et sl.		<u> </u>		; ··		
	АН	6,136,636	10-2000	Wu				:		
	Al	6,033,998	03-2000	Aronowitz et al.				: :		
	AJ.	6,057,220	05-2000	Ajmera et al.		}		₹.		
<u> </u>	AK	.6,087,229	07-2000	Aronowitz et al.			 	1		
AC.	AL	5,998,253	12-1999	Loh et al.			<u> </u>			
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	AB	6,225,167 B1	05-2001	Yu et al.						
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	AÈ	6,146,948	11-2000	Wu et al.						
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	AK	6,201,303	03-2001	Ngo et al.				, , ,	ÿ	
AG	AL	6,399,445	06-2002	· Hattangady et al.					<u>.</u>	
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Form PTO-144	19		EPARTMENT OF COMMERCE	ATTY, DOCKET I	NO.	SER 09/60	SERIAL NO. PRIORITY 09/602,381			
		LIST OF ART CITED BY APPLICANT (Use several sheets if occessary)			APPLICANT Micton Technology	, Inc.				
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	AB	6,080,629	06-2000	Gardner et al.						
	AC	5,970,345	10-1999	Hattangady et al.						
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	AJ	6,207,586	03-2001	Ma et al.	•					
N	AK	5,837,592	11-1998	Chang et al.				5 . . 6 5		
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Form PTO-14	449		U.S. D	EPARTMENT OF COMMERCE	ATTY. DOCKET I	SER1 09/60	SERIAL NO. PRIORITY 09/602,381			
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	AB	6,436,771 B1	08-2002	Jang et al.						
	AC	6,413,881	07-2002	Aronowitz et al.					,	
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